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DIALOG(R)File 347:JAPIO

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02336872 \*\*Image available\*\*  
FILM FORMING APPARATUS

PUB. NO.: 62-253772 A]  
PUBLISHED: November 05, 1987 (19871105)  
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#### ABSTRACT

PURPOSE: To prevent a film from depositing on the microwave introducing window of a plasma generator by placing a nozzle on the plasma blowoff side of the generator and feeding a film forming gas to the vicinity of the inflow whole of the nozzle so as to prevent the film forming gas from flowing backward.

CONSTITUTION: A nozzle 3 is placed on the plasma blowoff hole 2 side of a plasma generator 1 and a film forming gas is fed to the vicinity of the inflow hole 3a of the nozzle 3. The fed film forming gas is activated by contact with plasma and the activated gas is immediately transferred to the downstream side through the nozzle 3. Even when the spouted film forming gas is dispersed on the downstream side, the strong flow in the nozzle 3 prevents the gas from flowing backward. Accordingly, a film is prevented from depositing on the microwave introducing window 4 of the plasma generator 1 and continuous film formation can be carried out for a long time.

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DIALOG(R)File 351:Derwent WPI

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Film forming machine - has nozzle fitted to perforated partition wall between evacuated wafer chamber and plasma generating chamber to introduce reaction gas

Patent Assignee: CANON KK (CANO )

Number of Countries: 001 Number of Patents: 001

Patent Family:

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Abstract (Basic): JP 62253772 A

The machine comprises a plasma generating chamber including a microwave tube and a pipe for introducing reaction gas, an evacuated chamber including a wafer holder and isolated from the plasma chamber by a perforated partition wall, and a nozzle fitted to the perforation of the partition wall for admitting activated reaction gas from the plasma chamber into the wafer chamber.

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Derwent Class: M13